
Symposium (Oral) | Symposium | Film Formation and Low Temperature of IV Element Semiconductor

[7p-C18-1~11]Film Formation and Low Temperature of IV Element Semiconductor

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Thu. Sep 7, 2017 1:30 PM - 6:30 PM C18 (C18)

△：奨励賞エントリー

▲：英語発表

▼：奨励賞エントリーかつ英語発表

空欄：どちらもなし

3:30 PM - 4:00 PM

[7p-C18-5]Process Technology of Chemical Vapor Deposition for LTPS

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Keywords:chemical vapor deposition, low temperature poly silicon, mass production equipment

ULVAC continues to provide mass production equipments for several film formation processes from the start of mass production of the LTPS display in the 1990s to the present. In LTPS mass production, sputtering equipments are used for metal / TCO film and PECVD equipments are used for semiconductors and insulator films. We will introduce hardware technology and process technology using our PECVD system to form precursor film for Si crystallization and other layers. Also, I would like to mention about future applications and necessary technologies.